

AMENDMENTS TO THE CLAIMS

Claims 1-11 (canceled)

Claim 12 (original): A substrate processing method for processing a substrate to be processed, by supplying processing gas and solvent vapor to the substrate accommodated in a processing container, the method comprising the steps of:

researching on a pressure of the solvent vapor in a condition before the solvent vapor is supplied into the processing container;

supplying the solvent vapor into the processing container on the basis of the pressure of the solvent vapor.

Claim 13 (original): A substrate processing method as claimed in Claim 12, wherein the researching step for the pressure of the solvent vapor in the condition before being supplied into the processing container, is carried out by firstly measuring a temperature of the solvent vapor in the condition before being supplied into the processing container and secondly calculating the pressure from the detected temperature.

Claim 14 (original): A substrate processing method as claimed in Claim 12, wherein the researching step for the pressure of the solvent vapor in the condition before being supplied into the processing container is carried out by firstly measuring a temperature of a liquid solvent that can generate the solvent vapor to be supplied into the processing container and secondly calculating the pressure from the detected temperature.

Claim 15 (original): A substrate processing method as claimed in Claim 12, further comprising the step of supplying the processing gas into the processing container before supplying the solvent vapor into the processing container.

Claim 16 (original): A substrate processing method for processing a substrate to be processed, by supplying processing gas and solvent vapor to the substrate accommodated in a processing container, the method comprising the steps of:

supplying the processing gas into the processing container;

elevating a pressure of the solvent vapor before being supplied into the processing container higher than a pressure of the processing gas in the processing container; and

supplying the solvent vapor, whose pressure has been elevated higher than the pressure of the processing gas in the processing container, into the processing container.

Claim 17 (original): A substrate processing method as claimed in Claim 16, further comprising the step of controlling the pressure of the solvent vapor so as to be higher than a pressure of an atmosphere in the processing container, under condition that the pressure of the solvent vapor before being supplied into the processing container becomes higher than the pressure of the processing gas in the processing container.

Claim 18 (original): A substrate processing method as claimed in Claim 17, wherein the step of controlling the pressure of the solvent vapor so as to be higher than the pressure of the atmosphere in the processing container is carried, in a closed space where the solvent vapor before being supplied into the processing container is present, by releasing the closed space for a constant period to discharge the solvent vapor of a constant quantity from the closed space so that the pressure of the solvent vapor becomes less than a first pressure which is higher than the pressure of the processing gas in the processing container.

Claim 19-27 (canceled)